

## ABSTRACT OR SUPPORTING INFORMATION

**Presentation/Publication Information:**

Talk to be given by Bryan Biegel at the American Physical Society (APS) Centennial Meeting, March 23, 1999, Atlanta, GA. This material will also be published on the Web. A copy of the presentation is attached.

**Acknowledgments:**

This work was supported under NASA contract NAS2-14303.

**Abstract:**

We show that quantum effects are likely to significantly degrade the performance of MOSFETs as these devices are scaled below 100 nm channel length and 2 nm oxide thickness over the next decade. A general and computationally efficient electronic device model including quantum effects would allow us to monitor and mitigate these effects. Full quantum models are too expensive in multi-dimensions. Using a general but efficient PDE solver called PROPHET, we implemented the density-gradient (DG) quantum correction to the industry-dominant classical drift-diffusion (DD) model. The DG model efficiently includes quantum carrier profile smoothing and tunneling in multi-dimensions and for any electronic device structure. We show that the DG model reduces DD model error from as much as 50% down to a few percent in comparison to thin-oxide MOS capacitance measurements. We also show the first DG simulations of gate oxide tunneling and transverse current flow in ultra-scaled MOSFETs. The advantages of rapid model implementation using the PDE solver approach will be demonstrated, as well as the applicability of the DG model to any electronic device structure.

# Multi-Dimensional Quantum Tunneling and Transport Using the Density-Gradient Model

Bryan A. Biegel

MRJ Technology Solutions

NASA Ames Research Center, NAS Division

## Collaborators

Dr. Zhiping Yu (Stanford University)

Dr. Mario Ancona (Naval Research Laboratory)

Dr. Conor Rafferty (Lucent Technologies)

biegel@nas.nasa.gov, <http://science.nas.nasa.gov/~biegel>

Bryan Biegel

NAS Division, NASA Ames Research Center

MRJ, Inc.

# Multi-Dimensional Quantum Tunneling and Transport Using the Density-Gradient Model

## Outline

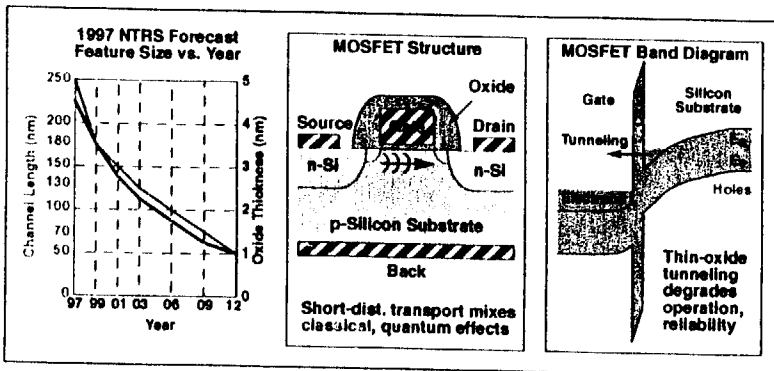
- Motivation
- Density-Gradient Model
- Quantum Confinement
- Quantum Tunneling
- Conclusions

Bryan Biegel

NAS Division, NASA Ames Research Center

MRJ, Inc.

# Tunneling and Transport in MOSFETs



Need 2-D/3-D electronic transport model with quantum effects, but...

- Quantum computations still too slow
- Drift-diffusion (classical) model is industry work-horse

Bryan Biegel

NAS Division, NASA Ames Research Center

MRJ, Inc.

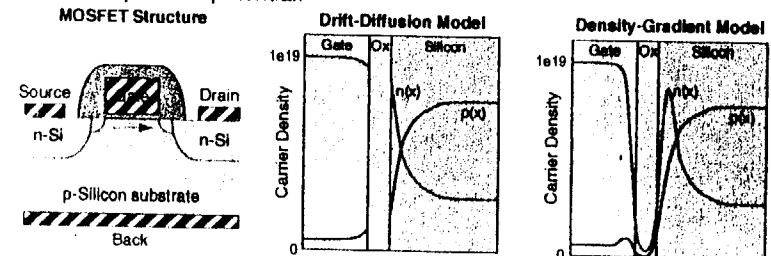
# Density-Gradient Model

Density-Gradient Model (quantum-corrected drift-diffusion):

$$\frac{\partial n}{\partial t} = \nabla \cdot [D_n \nabla n - n \mu_n \nabla (u + u_{qn})] \quad u_{qn} \equiv 2b_n \left( \frac{\nabla^2 \sqrt{n}}{\sqrt{n}} \right) \quad b_n \equiv \frac{-\hbar^2}{12m_n^*q}$$

$$\frac{\partial p}{\partial t} = \nabla \cdot [D_p \nabla p + p \mu_p \nabla (u + u_{qp})] \quad u_{qp} \equiv -2b_p \left( \frac{\nabla^2 \sqrt{p}}{\sqrt{p}} \right) \quad b_p \equiv \frac{\hbar^2}{12m_p^*q}$$

Effect of quantum potential:



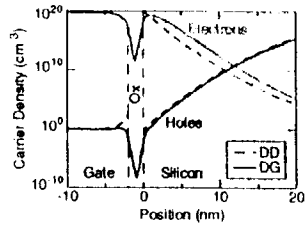
Bryan Biegel

NAS Division, NASA Ames Research Center

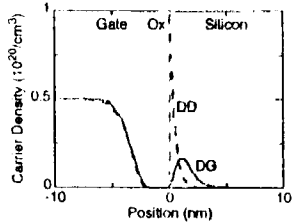
MRJ, Inc.

## Quantum Confinement - Carrier Profiles

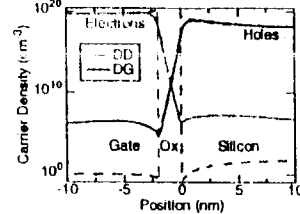
Channel Inversion ( $V_G=1V$ )



Channel Inversion ( $V_G=1V$ )



Channel Accum. ( $V_G=-1.5V$ )

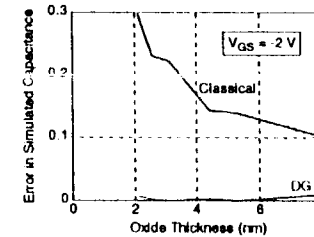
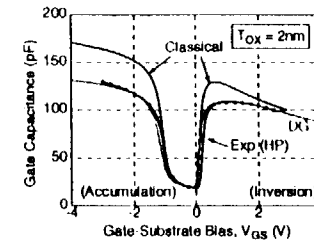
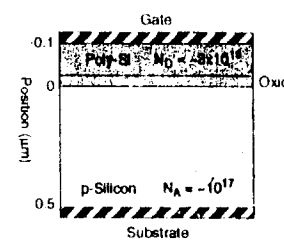


### Conclusions:

- Quantum confinement significantly changes inversion charge profile
- Densities decrease exponentially into oxide

## MOS Gate Capacitance

1-D MOS Capacitor Model

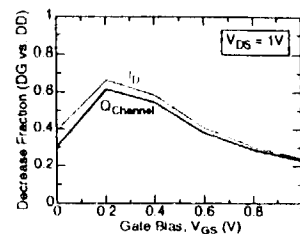
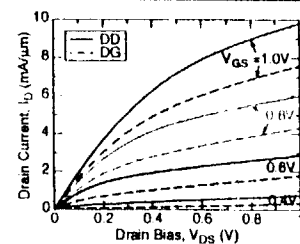
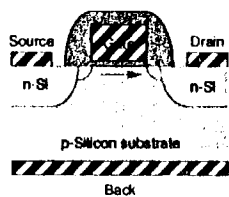


### Conclusions:

- DG model greatly improves accuracy
- Classical model diverges rapidly below  $T_{OX} = 4nm$

## 30 nm MOSFET - Drain Characteristic

2-D MOSFET Model

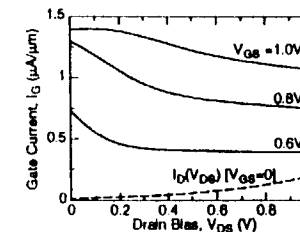
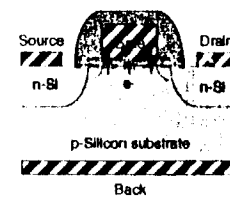


### Conclusions:

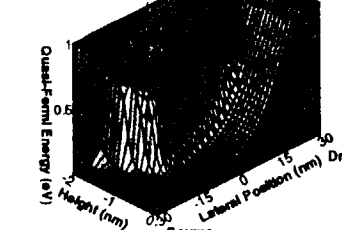
- MOSFET still works at 30nm channel length!
- Quantum effects reduce current by up to 60%
- Current decrease due to reduced channel charge

## 30 nm MOSFET - Gate Oxide Tunneling

2-D MOSFET Model



Tunnel Current Profile (In Oxide)



### Conclusions:

- Gate leakage decreases with increasing drain bias
- Gate leakage greater than OFF drain current
- Tunnel current highest near source, drain

## Conclusions

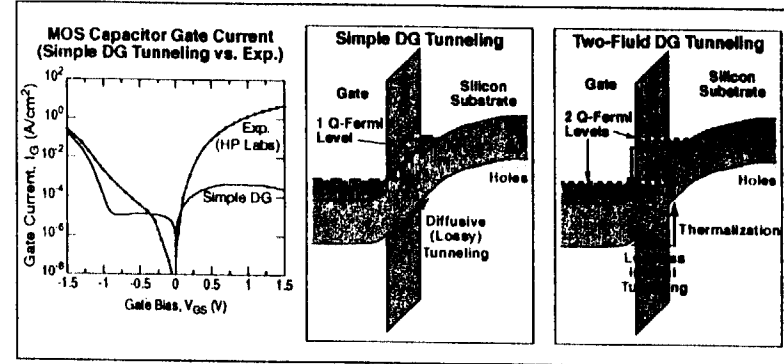
- Density-Gradient transport model:
  - Similar to industry standard model (DD)
  - Moderate additional computation
  - Quantum confinement, tunneling
- Simulated quantum effects
  - MOS Capacitor: dramatic improvement in accuracy
  - Small MOSFET:  $I_D$  decrease =  $Q_{\text{Channel}}$  decrease
  - First 2-D DG tunneling: S/D tunneling "hot-spots"

## Future DG Tunneling Model

Simple Density-Gradient model assumes diffusive tunneling!

Under development: "two-fluid", lossless, inertial tunneling model

Why?



How? PROPHET: Script-based PDE solver (Lucent Technologies)